

10/657,449, CA Reg. F.U. STRUC. SEARCH, 3/21/06, RQX
Formulae cl 1

RE.CNT 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

=> d his

(FILE 'HOME' ENTERED AT 14:18:50 ON 21 MAR 2006)

FILE 'REGISTRY' ENTERED AT 14:19:01 ON 21 MAR 2006

L1 STRUCTURE uploaded
L2 STRUCTURE uploaded
L3 3125 S L1 FULL
L4 18776 S L2 FULL

FILE 'CAPLUS' ENTERED AT 14:21:48 ON 21 MAR 2006

L5 362 S L3
L6 1433 S L4
L7 42960 S PHOTORESIST OR RESIST COMPOSITION
L8 1 S L5 AND L7
L9 5 S L6 AND L7

=> d 19 1-5 bib ab hitstr

L9 ANSWER 1 OF 5 CAPLUS COPYRIGHT 2006 ACS on STN
AN 2004:963502 CAPLUS

DN 141:417925

TI Positive-working vacuum-UV photoresist composition and patterning method using the same

IN Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 99 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004318046	A2	20041111	JP 2003-293188	20030813
PRAI	JP 2003-94329	A	20030331		

AB Disclosed is the pos.-working vacuum-UV photoresist composition especially suited for a F2 excimer laser (157 nm) comprising (a) a resin having a repeating unit FR0C-CFR1, FR0C-CF(OR2), and/or F(R3O)C-CFR4 (R0,1 = H, F, alkyl, cycloalkyl, etc.; R2-4 = alkyl, cycloalkyl, etc.), and (b) a photoacid.

IT 791853-95-7

RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)

(pos.-working vacuum-UV photoresist composition containing fluoropolymer and photoacid)

RN 791853-95-7 CAPLUS

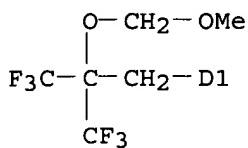
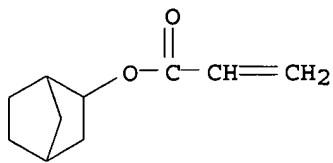
CN 2-Propenoic acid, 5(or 6)-[3,3,3-trifluoro-2-(methoxymethoxy)-2-(trifluoromethyl)propyl]bicyclo[2.2.1]hept-2-yl ester, polymer with N-[5,6-bis(hydroxymethyl)bicyclo[2.2.1]hept-2-yl]-2-fluoro-2-propenamide and tetrafluoroethene (9CI) (CA INDEX NAME)

CM 1

CRN 791853-94-6

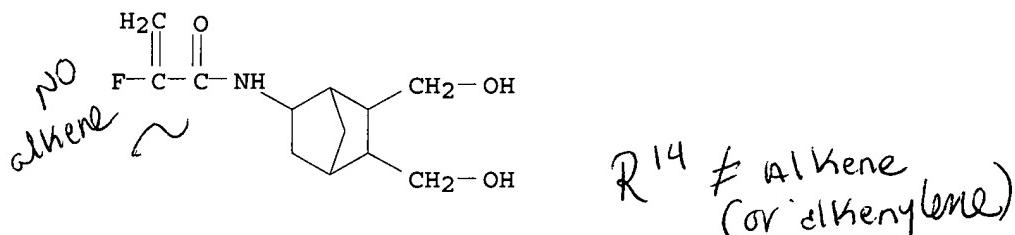
CMF C16 H20 F6 O4

CCI IDS



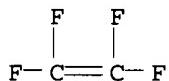
CM 2

CRN 791853-93-5
CMF C12 H18 F N O3



CM 3

CRN 116-14-3
CMF C2 F4



L9 ANSWER 2 OF 5 CAPLUS COPYRIGHT 2006 ACS on STN

AN 2004:801603 CAPLUS

DN 141:304291

TI Positive photoresist compositions showing high transparency to 157-nm F2 excimer lasers and forming patterns with small line-edge roughness and less scums

IN Kanda, Hiromi; Mizutani, Kazuyoshi; Kanna, Shinichi

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 68 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004271630	A2	20040930	JP 2003-58733	20030305
PRAI	JP 2003-58733		20030305		
AB	The compns. comprise (A) resins having (A1) [R1R2CCR3(OR4)] units [R1-R3 = H, (fluoro)alkyl, F; R4 = H, (fluoro)alkyl, L1X; X = polar group, alkaline				

developer-soluble group, group solubilized in alkaline developers by acids; L1
= single bond, divalent linking group] and (A2) [R5R6CCR7(CONR8R9)] units
[R5-R7 = same as R1; R8, R9 = H, (fluoro)alkyl, L2Y; Y = same as X; L2 =
same as L1] and (B) compds. generating acids by (actinic ray) radiation.

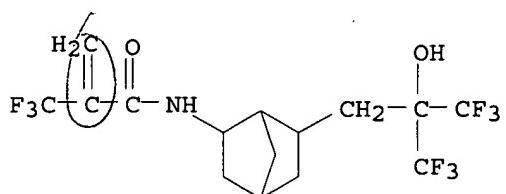
IT 762301-12-2P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT
(Reactant or reagent)

(monomers; pos. photoresist compns. showing high transparency
to F2 excimer lasers and forming patterns with small line-edge
roughness and less scums)

RN 762301-12-2 CAPLUS

CN 2-Propenamide, N-[6-[3,3,3-trifluoro-2-hydroxy-2-
(trifluoromethyl)propyl]bicyclo[2.2.1]hept-2-yl]-2-(trifluoromethyl)-
(9CI) (CA INDEX NAME)



IT 762301-13-3P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)

(pos. photoresist compns. showing high transparency to F2
excimer lasers and forming patterns with small line-edge roughness and
less scums)

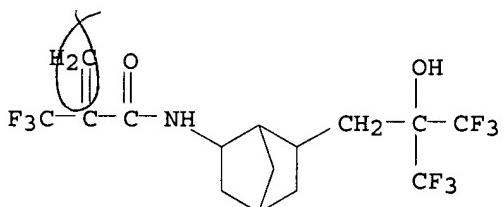
RN 762301-13-3 CAPLUS

CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 6-(ethenyloxy)-2-
(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with
N-[6-[3,3,3-trifluoro-2-hydroxy-2-(trifluoromethyl)propyl]bicyclo[2.2.1]he
pt-2-yl]-2-(trifluoromethyl)-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 762301-12-2

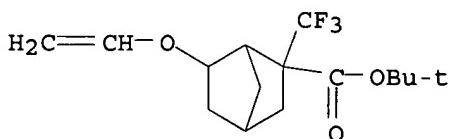
CMF C15 H16 F9 N O2



CM 2

CRN 634920-64-2

CMF C15 H21 F3 O3

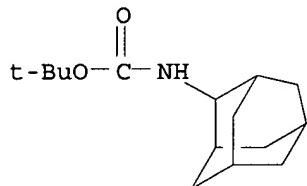


L9 ANSWER 3 OF 5 CAPLUS COPYRIGHT 2006 ACS on STN
 AN 2004:631975 CAPLUS
 DN 141:181966
 TI Proton-neutralizing agent and photoresist containing the same
 IN Kuzuha, Noboru
 PA Aibaitsu K. K., Japan
 SO Jpn. Kokai Tokkyo Koho, 10 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN.CNT 1

NO DATE

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2004217867	A2	20040805	JP 2003-9721	20030117
PRAI JP 2003-9721		20030117		

AB The agent well neutralizes proton generated in dark during the storage of photoresist and is inert under exposure of the resist.
 IT 733037-96-2P
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (proton-neutralizing agent and photoresist containing the same)
 RN 733037-96-2 CAPLUS
 CN Carbamic acid, tricyclo[3.3.1.13,7]dec-2-yl-, 1,1-dimethylethyl ester (9CI) (CA INDEX NAME)



L9 ANSWER 4 OF 5 CAPLUS COPYRIGHT 2006 ACS on STN
 AN 2004:219910 CAPLUS
 DN 140:278422
 TI Chemical amplification type resist composition
 IN Takata, Yoshiyuki; Yoshida, Isao; Nakanishi, Hirotoshi
 PA Sumitomo Chemical Company, Limited, Japan
 SO U.S. Pat. Appl. Publ., 22 pp.
 CODEN: USXXCO
 DT Patent
 LA English
 FAN.CNT 1

my app!

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI US 2004053171	A1	20040318	US 2003-657149	20030909
CN 1488996	A	20040414	CN 2003-156561	20030909
JP 2004126572	A2	20040422	JP 2003-319438	20030911
PRAI JP 2002-266539	A	20020912		
OS MARPAT 140:278422				

AB The present invention provides a chemical amplification type pos. resist composition comprising (1) a nitrogen containing compound of the formula A(-X-N(R₁₃)C(=O)R₁₄)_n or A(-X-C(=O)N(R₁₅)R₁₆)_n (A = alicyclic hydrocarbon group; X = C₁₋₄ alkylene, single bond; R₁₃₋₁₆ = H, C₁₋₁₂ alkyl, C₃₋₁₂ cycloalkyl, C₁₋₁₂ haloalkyl, etc.; n = 1-5); (2) resin which contains a structural unit having an acid labile group and which itself is insol. or poorly soluble in an alkali aqueous solution but becomes soluble in an alkali aqueous solution by the action of an acid; and (3) an acid generator of the formula I (Q1-5

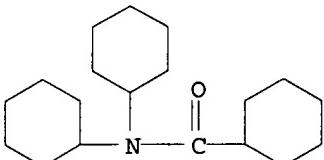
=H, hydroxyl, C1-12 alkyl, alkoxy; Z+ = II (P1-3 = H, hydroxyl, C1-6 allyl and alkoxy), III (P4,5 = H, hydroxyl, C1-6 allyl and alkoxy), P6P7S+-CH(P8)C(=O)P9 (P6,7 = C1-6 alkyl, C3-10 cycloalkyl, etc.; P8 = H; P9 = C1-6 alkyl, C3-10 cycloalkyl, aromatic group, etc.)).

IT 550309-32-5P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(chemical amplification type resist composition containing)

RN 550309-32-5 CAPLUS

CN Cyclohexanecarboxamide, N,N-dicyclohexyl- (9CI) (CA INDEX NAME)



L9 ANSWER 5 OF 5 CAPLUS COPYRIGHT 2006 ACS on STN

AN 2003:671498 CAPLUS

DN 139:188320

TI Positive photoresists showing superior transparency to 157-nm light and excellent sensitivity

IN Sasaki, Tomoya; Mizutani, Kazuyoshi; Kanna, Shinichi

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 46 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003241381	A2	20030827	JP 2002-46284	20020222
PRAI	JP 2002-46284		20020222		

AB The photoresists, useful for F2 excimer laser lithog., comprise (A) resins increasing alkali solubility upon acid action and having repeating unit CR1R2CR3(L1XNHR4) (R1-R3 = H, Cl, CN, Me, F, fluoroalkyl, where ≥ 1 of them is F or fluoroalkyl; L1 = single bond, bivalent bridging group; X = CO, SO₂; R4 = monovalent organic group) and (B) radiation-sensitive acid generators.

IT 581804-50-4P 581804-51-5P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(binders; chemical amplified pos. photoresists containing fluoro-containing acid-labile binders showing high transparency to 157-nm light)

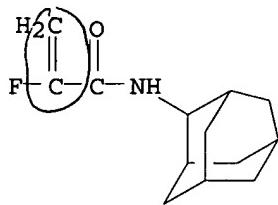
RN 581804-50-4 CAPLUS

CN 2-Propenamide, 2-fluoro-N-tricyclo[3.3.1.13,7]dec-2-yl-, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene (9CI) (CA INDEX NAME)

CM 1

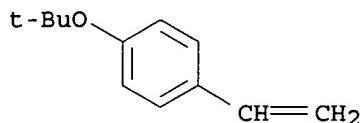
CRN 581804-48-0

CMF C13 H18 F N O



CM 2

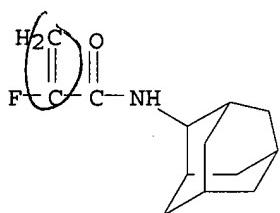
CRN 95418-58-9
CMF C12 H16 O



RN 581804-51-5 CAPLUS
CN 2-Propenamide, 2-fluoro-N-tricyclo[3.3.1.13,7]dec-2-yl-, polymer with 1-cyclohexyl-4-[2-[1-(4-ethenylphenoxy)ethoxy]ethoxy]benzene (9CI) (CA INDEX NAME)

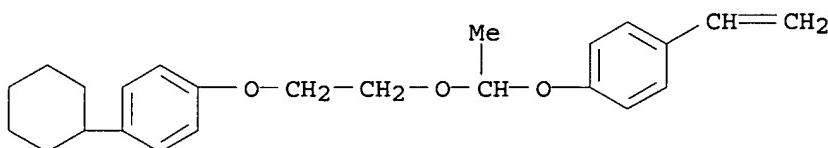
CM 1

CRN 581804-48-0
CMF C13 H18 F N O



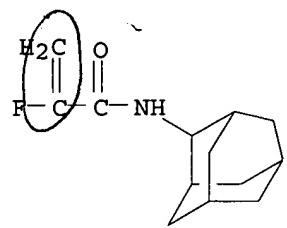
CM 2

CRN 326591-95-1
CMF C24 H30 O3



IT 581804-48-0P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(chemical amplified pos. photoresists containing fluoro-containing acid-labile binders showing high transparency to 157-nm light)
RN 581804-48-0 CAPLUS

CN 2-Propenamide, 2-fluoro-N-tricyclo[3.3.1.13,7]dec-2-yl- (9CI) (CA INDEX
NAME)



=>

L8 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN

AN 2005:135411 CAPLUS

DN 142:219688

TI Cyclic dithiocarbonates, their preparation and applications

IN Motokicho, Suguru; Sudo, Atsushi; Endo, Takeshi; Itagaki, Yoshiteru; Kaneko, Ryosuke; Uenishi, Kazuya; Karim, Sikder Mohammad Abdul

PA Henkel Kommanditgesellschaft Auf Aktien, Germany

SO Eur. Pat. Appl., 22 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1506964	A1	20050216	EP 2003-18503	20030815
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	WO 2005016908	A1	20050224	WO 2004-EP2655	20040315
	W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
	RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				

PRAI EP 2003-18503 A 20030815

OS MARPAT 142:219688

AB The present invention relates to cyclic 5-membered ring dithiocarbonate compds. of the general formula I, wherein R1, R2, and R3 are the same or different, each of which denotes hydrogen or a C1-4 straight-chain or branched alkyl. The invention further relates to a process for producing these compds. and a variety of products obtainable by reacting the title compds. such as monomers for polymers useful for coating, adhesive, sealing composition, photoresist, etc. Thus, silylating glycidol with trimethylsilyl chloride gave glycidyl trimethylsilyl ether (II). Reacting II with CS2 in the presence of LiBr in THF gave a dithiocarbonate having silyl ether which was desilylated to give 5-hydroxymethyl-1,3-oxathiolane-2-thione (III). Reacting III with piperazine and subsequently oxidatively polymerizing the adduct gave a disulfide-containing thio urethane polymer having OH groups which could be further modified, e.g., by acetylation.

IT 843641-80-5DP, reaction products with epoxy resins and crosslinkers

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(manufacture of cyclic dithiocarbonates useful for monomers and their applications)

RN 843641-80-5 CAPLUS

CN Carbamic acid, [1,3-cyclohexanediylbis(methylene)]bis-, bis[(2-thioxo-1,3-oxathiolan-5-yl)methyl] ester (9CI) (CA INDEX NAME)

